PATENT NUMBER and ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 10080319	FILING DATE 02/21/2002	CLASS 430	SUBCLASS	GAU 1753	EXAMINER THURNTON				
**APPLICANTS: Lee Geun; Jung Jae; Shin Ki;									
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** FOREIGN APPLICATIONS VERIFIED:									
REPUBLIC OF KOREA 2001-38026 06/29/2001									
PG-PUB DO N	OT PUBLISH 🗖		RESCIN	_D 🗀					
Foreign prior⊕y clair 35 USC 119 condition		yes yes	⊒ no ⊒ no	•	ATTORNEY DOCKET NO				
Verified and Acknowledged Examiners's initials y CT 30205/38088									
TITLE: Photoresist monomers, polymers thereof and photoresist compositions containing the same U.S.DEPT. OF COMM.PATA.TM. PTO-435L(Rev. 12-94)									

NOTICE OF ALLOWANCE MAILED			CLAIMS ALLOWED					
ISSUE FEE		Assistant Examiner	Total Claims	Print Claim for O.G				
			DRAWING					
Amount Due	Date Paid		Sheets Drwg.	Figs.Dn	I	Print Fig.		
TERMINAL DISCLAMER		Primary Examiner	Application Examiner					
		PREPARED FOR ISSUE Application Examiner WARNING: The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35, Sections 122, 181 and 368, Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.						
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